



(19)

(11) Publication number:

Generated Document.

## PATENT ABSTRACTS OF JAPAN

(21) Application number: 04134135

(51) Intl. Cl.: C07F 7/18

(22) Application date: 27.04.92

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| <p>(30) Priority:</p> <p>(43) Date of application publication: 19.11.93</p> <p>(84) Designated contracting states:</p> | <p>(71) Applicant: SHIN ETSU CHEM (</p> <p>(72) Inventor: YAMATANI MASAAI<br/>YANAGISAWA HIDE</p> <p>(74) Representative:</p> |
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(54) **PRODUCTION OF @  
(3754/24)METH)ACRYLIC  
FUNCTIONAL GROUP-  
CONTAINING  
ORGANOSILICON  
COMPOUND**

(57) Abstract:

**PURPOSE:** To easily obtain the subject compound in high yield using inexpensive, easy-to-handle raw materials by reaction of a (meth) acrylic acid with an organosilicon compound having halogen-substituted hydrocarbon group in the presence of a cyclic structure-contg. tertiary amine compound.

**CONSTITUTION:** A (meth)acrylic acid of formula I (R1 is CH3 or H) is dissolved in e.g. toluene, and a cyclic structure-contg. tertiary amine compound (e.g. 1,8-- diazabicyclo [5,4,0]undec-7ene) is added to the resulting solution and the reaction system is heated to 90°C followed by gradually dripping an organosilicon compound having Cl-or Br-substituted hydrocarbon group of formula II (X is Cl or Br; R2 is 1-10C divalent hydrocarbon; R3 is CH3 or CH2CH3; n is 1, 2 or 3) (e.g. X-

chloropropylmethyl dimethoxysilane) into the system. The resultant system is heated at 90-100°C for 3hr under agitation and aged, and then cooled, and a salt formed is filtered off; the filtrate is then distilled, thus obtaining the objective compound of formula III.

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